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THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re Application of:  
Mahorowala et al

Application No.: 09/902,728

Art Unit: 1756

Filed: July 12, 2001

Examiner: Barreca, N.M.

For: Method to Prevent Pattern Collapse in Features  
Etched in Sulfur Dioxide-Containing Plasmas

**AMENDMENT**

Box Issue Fee  
Commissioner for Patents  
P.O. Box 1450  
Alexandria, VA 22313-1450

Dear Sir:

As required by the Notice of Allowability dated August 25, 2004, please amend the above-identified U.S. patent application as follows:

**Amendments to the Drawings** are shown in the attached Replacement Sheets. The amendments include labelling the bottom figure on page 1, 2 and 4 of the drawings "Fig. 1B", "Fig. 2B" and "Fig. 4B", respectively.

Please charge any necessary fees or credit any overpayment to Deposit Account 22-0185.

Dated:

9/27/04

Respectfully submitted,

By

John A. Evans

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